



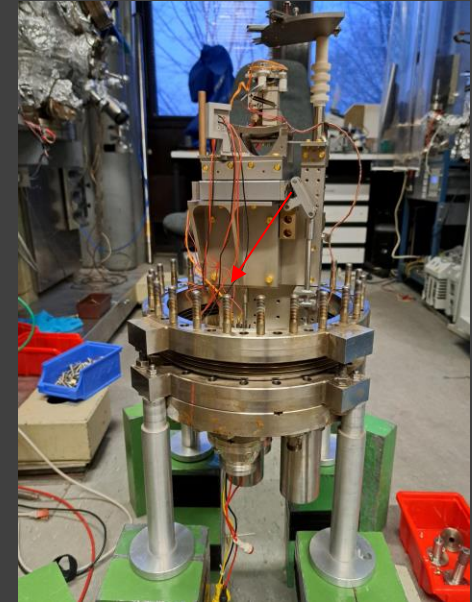
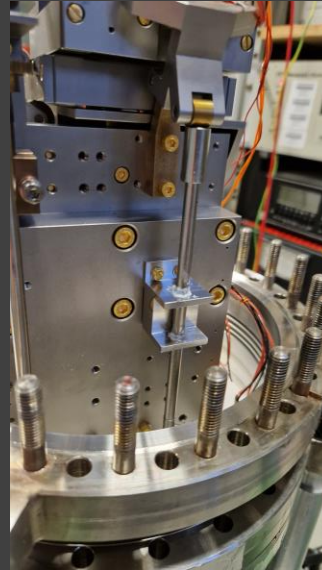
### 3. Novalis Meeting – Update BUW

Frederic Braun  
[fbraun@uni-wuppertal.de](mailto:fbraun@uni-wuppertal.de)  
Dirk Lützenkirchen-Hecht  
[dirklh@uni-wuppertal.de](mailto:dirklh@uni-wuppertal.de)



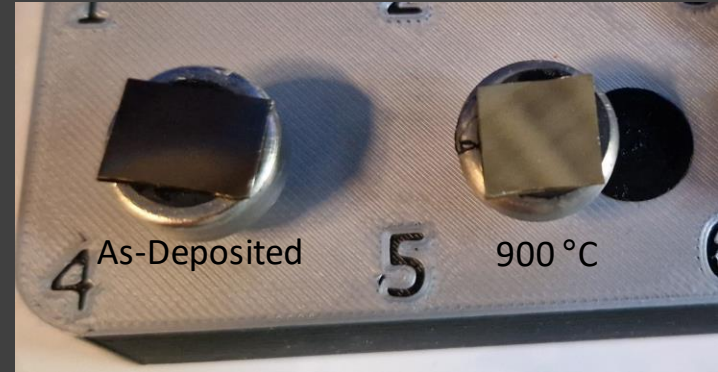
BERGISCHE  
UNIVERSITÄT  
WUPPERTAL

- Repair of the XYZ-Stage
  - Rods for X- and Y-axis had mechanical play in linear guides
    - New linear guides fixed the problem
- Baked out at 120 °C
  - Pressure in main chamber:  
 $8 \cdot 10^{-10}$  mbar
- FESM fully operational again



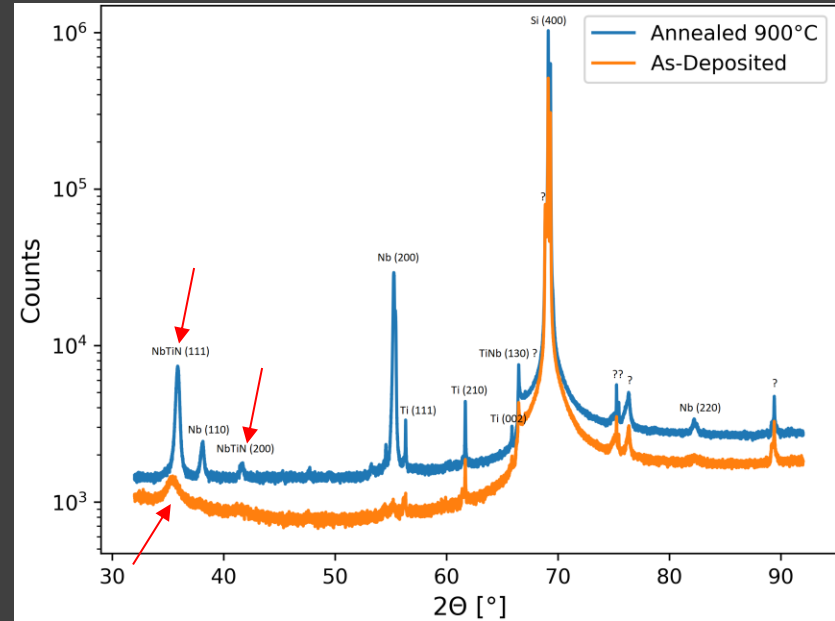
## New NbTiN samples

- Two NbTiN samples from Marc, Lea and Isabel
  - 60 nm NbTiN + 15 nm AlN on Si-Wafer
  - Both as-deposited and annealed at 900 °C
- Planned analysis:
  - XRD (first results)
  - OP / AFM (first results)
  - SEM
  - FESM



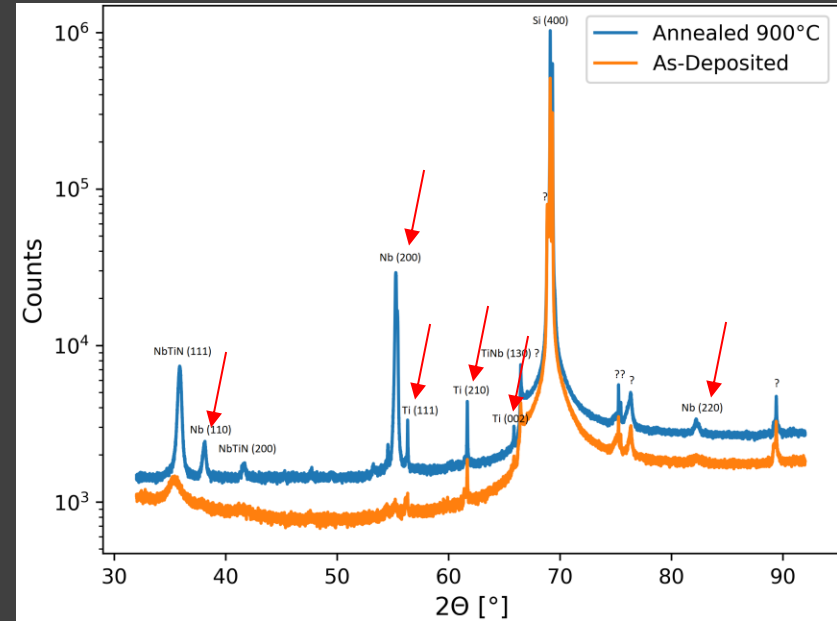
# XRD - Influence of annealing NbTiN

- NbTiN (111)-Peak shifts to larger angle
  - $\text{Nb}_{1-x}\text{Ti}_x\text{N}$  recombining to larger x
  - Could partly explain creation of Nb phases
- Sharper NbTiN (111)-Peak indicates growth in grain size
  - $L_{\text{ad},111} = (67.60 \pm 49.17) \text{ \AA}$  to  $L_{900^\circ\text{C},(111)} = (268.96 \pm 1.80) \text{ \AA}$
- Growths of NbTiN (200)-Phase
  - $L_{900^\circ\text{C},(200)} = (269.82 \pm 17.69) \text{ \AA}$



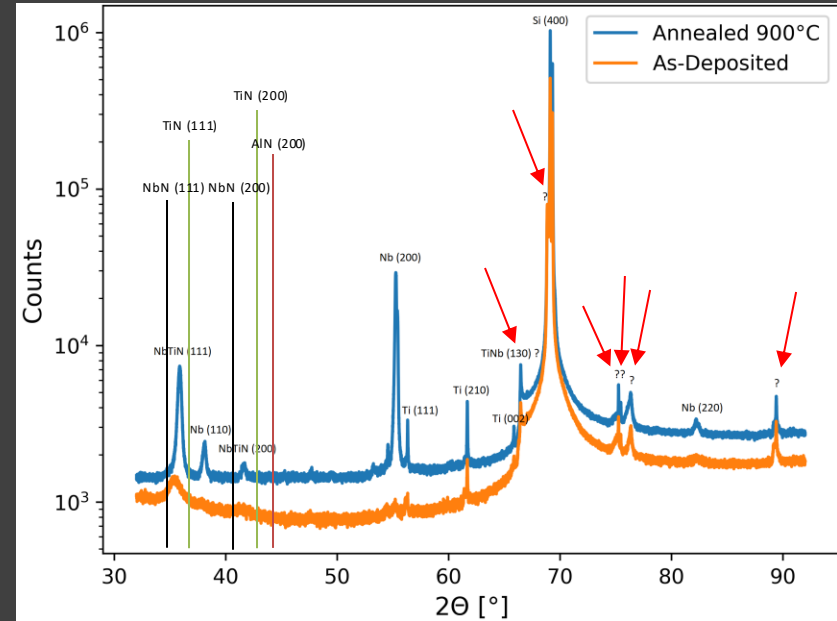
## XRD - Influence of annealing NbTiN

- Annealing leads to creation of elemental Nb-phases
- Both Ti- and Nb-peaks increase
- Decomposition of NbTiN to Nb and Ti
- Annealing under nitrogen atmosphere could slow down decomposition process



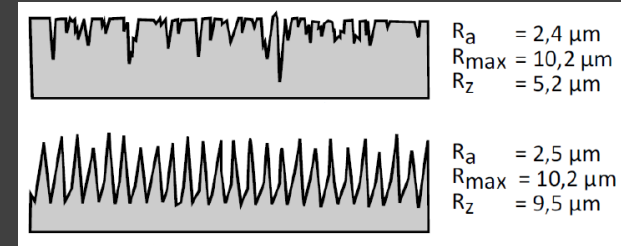
# XRD - Influence of annealing NbTiN

- Few unknown Peaks
  - AlN layer is too thin
  - Annealing should show changes in oxide phases
  - no TiN or NbN phases
- Grazing incidence XRD could show in which depth unknown structures are
- Potential TiNb (130) -peak at  $(66.47 \pm 0.01)^\circ$ 
  - Theoretical angle at  $66.821^\circ$ 
    - 0.45 % bigger lattice parameter due to stress
    - Annealing does not reduce stress



# Optical profilometer

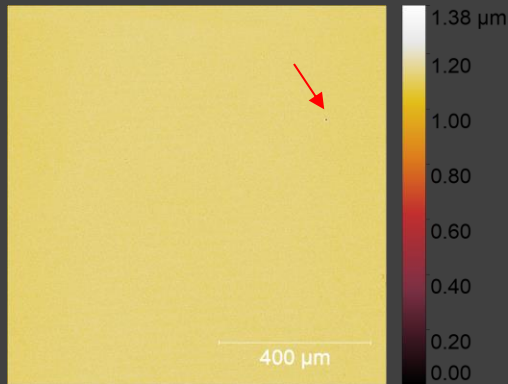
- White light irradiation and spectral reflection
  - Chromatic aberration
- Scanning range up to  $20 \times 20 \text{ cm}^2$
- $2 \text{ }\mu\text{m}$  lateral resolution
- $3 \text{ nm}$  vertical resolution
- For higher resolution the AFM can be used



- FE sensitive to peaks on the surface
  - $R_z$  relevant for determining the surface roughness for FE applications
- $R_z$  is the maximum peak to valley height

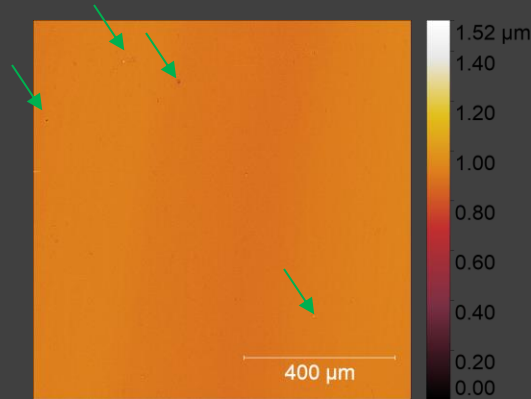


## OP – Surface roughness of NbTiN thin films



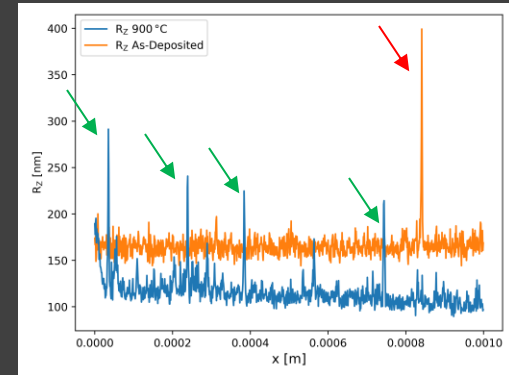
As-deposited

- $R_a = (23.80 \pm 0.62) \text{ nm}$
  - $R_z = (165.50 \pm 12.51) \text{ nm}$
- over  $10 \times 10 \text{ mm}^2$



Annealed 900 °C

- $R_a = (16.13 \pm 1.01) \text{ nm}$
  - $R_z = (116.30 \pm 18.25) \text{ nm}$
- over  $10 \times 10 \text{ mm}^2$



- Particles or defects on surface yield high  $R_{z,i}$  values
- Does not influence overall  $R_z$  too much

→ Annealing reduces  $R_a$  by 32.22 % and  $R_z$  by 29.73 %



## Summary and Outlook

- Grain size of NbTiN significantly increases due to annealing
- Surface roughness reduced by  $\approx 30\%$ 
  - Smaller surface peaks increases onset-field of FE
- XRD data shows decomposition of NbTiN due to annealing
  - Annealing under nitrogen atmosphere could slow down the process
- Looking forward to:
  - FESM measurements
    - I-V-curves
    - Constant current mapping
  - SEM and EDX measurements
  - Further analysis on XRD and OP data

Thank you for your  
attention!